

U.S. Patent Application of Tokmulin et al.  
Serial No.: 08/860,763  
Art Unit: 1763

through a geometric center thereof and perpendicular to a plane of said platform; said plasma jet and wafer holders being displaced with respect to each other and may be in or out of contact with each other, said plasma jet generator being located such that a plasma jet is directed upwardly in respect of a plane of said horizontal platforms of said wafer holders; cooling means associated with each horizontal platform in fluid flow communication with said gas supplying means and located such that resulting gas flows permit the positioning of the platform near a holder and improve cooling of individual areas over the wafer surfaces while avoiding the need to provide additional cooling of said plasma generator due to natural convection of the hot gases; a manipulator; storage devices for the wafers to be treated; and a closed chamber having a gas exchange system with the wafer holders and a plasma jet generator located inside said chamber.

Claim 5, line 1, change "4" to -14-.

## REMARKS

This Amendment is responsive to the Office Action mailed April 25, 2000. The Examiner's comments have been carefully considered.

Claims 2 and 6 have been rejected as being fully anticipated by the Gasworth patent for reasons set forth in paragraph 4 of the Office Action, while claim 3 has been rejected as being obvious on the basis of Gasworth in view of or when combined with the Japanese Publication JP4-124092 or Ikegaya, for reasons set forth in paragraph 6 of the Office Action. However, it is